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## U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>J.H.</i>	AA	6,187,679	2/13/01	Cabral, Jr. Et al.			
<i>J.H.</i>	AB	6,362,086	3/26/02	Weimer et al.			
<i>J.H.</i>	AC	5,852,319	12/22/98	Kim et al.			
<i>J.H.</i>	AD	5,997,634	12/7/99	Sandhu et al.			
<i>J.H.</i>	AE	6,090,708	7/18/00	Sandhu et al.			
<i>J.H.</i>	AF	6,306,766	10/23/01	Sandhu et al.			
	AG						
	AH						
	AI						
	AJ						

## FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AK							
	AL							

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

<i>J.H.</i>	AM		'Mechanisms for enhanced C54-TiSi <sub>2</sub> formation in Ti-Ta alloy films on single-crystal Si'; A. Quintero et al.; Journal of Materials Research; Vol. 14, No. 12 Dec. 1999 pp. 4690-4700					
<i>J.H.</i>	AN		'Enhanced formation of the C54 TiSi <sub>2</sub> by an interposed layer of molybdenum'; A. Mouroux et al.; Appl. Phys. Lett. 69 (7), 12 August 1996; ©1996 American Institute of Physics					
<i>J.H.</i>	AO		'Low temperature formation of C54-TiSi <sub>2</sub> using titanium alloys'; C. Cabral, Jr. Et al; Appl. Phys. Lett. 71 (24) 15 December 1997 ©1997 American Institute of Physics; pp. 3531-3533					
	AP							

EXAMINER

*Lynne A. Hurley*

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*9/18/04*

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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